- 61. An electric device according to claim 60, wherein said Pb-free solder is also directly in contact with said substrate.
- 62. An electronic device according to claim 6, wherein said Sn-Bi alloy layer is directly in contact with said lead or directly in contact with a Cu layer in contact with said lead, and said Pb-free solder is directly in contact with said Sn-Bi alloy layer.
- 63. An electric device according to claim 62, wherein said Pb-free solder is also directly in contact with said substrate.
  - 64. An electronic device according to claim 11, wherein said Sn-Bi alloy layer is directly in contact with said lead or directly in contact with a Cu layer in contact with said lead, and said Pb-free solder is directly in contact with said Sn-Bi alloy layer.
  - 65. An electric device according to claim 64, wherein said Pb-free solder is also directly in contact with said substrate.
  - 66. An electronic device according to claim 19, wherein said Sn-Bi alloy layer is directly in contact with said lead or directly in contact with a Cu layer in contact with said lead, and said Pb-free solder is directly in contact with said Sn-Bi alloy layer.

- 67. An electric device according to claim 66, wherein said Pb-free solder is also directly in contact with said substrate.
- 68. An electronic device according to claim 24, wherein said Sn-Bi alloy layer is directly in contact with said lead or directly in contact with a Cu layer in contact with said lead, and said Pb-free solder is directly in contact with said Sn-Bi alloy layer.
- 69. An electric device according to claim 68, wherein said Pb-free solder is also directly in contact with said substrate.
- 70. An electronic device according to claim 43, wherein said Sn-Bi alloy layer is directly in contact with said first electrode or directly in contact with a Cu layer on the first electrode, and the solder is directly in contact with the Sn-Bi alloy layer.
- 71. An electronic device according to claim 70, wherein said solder is directly in contact with the second electrode.
- 72. An electronic device according to claim 50, wherein said Sn-Bi alloy layer is directly in contact with said first electrode or directly in contact with a Cu layer on the first electrode, and the solder is directly in contact with the Sny-Bi alloy layer.
- 73. An electronic device according to claim 72, wherein said solder is directly in contact with the second electrode.

- 74. An electronic device according to claim 51, wherein said Sn-Bi alloy layer is directly in contact with said first electrode or directly in contact with a Cu layer on the first electrode, and the solder is directly in contact with the Sn-Bi alloy layer.
- 75. An electronic device according to claim 74, wherein said solder is directly in contact with the second electrode.
- 76. An electronic device according to claim 59, wherein said Sn-Bi alloy layer is directly in contact with said first electrode or directly in contact with a Cu layer on the first electrode, and the solder is directly in contact with the Sn-Bi alloy layer.
- 77. An electronic device according to claim 76, wherein said Sn-Bi alloy layer is directly in contact with said first electrode or directly in contact with a Cu layer on the first electrode, and the solder is directly in contact with the Sn-Bi alloy layer.
  - 78. An electronic device comprising:

a semisonductor device having an electrode structure which comprises a lead and a Sn-Bi alloy layer containing 1-5 wt% Bi which is formed directly on the lead;

a circuit board which is connected to the semiconductor device with a solder which is made of Pb-free alloy,

wherein the connection is formed by contacting and soldering the Sn-Bi alloy layer and the solder.

- 79. An electronic device according to claim 78, wherein the Pb-free solder comprises Sn, Ag and Bi.
- 80. An electronic device according to claim 78, wherein the Pb-free solder comprises Sn, Ag, Bi and Cu.
- 81. An electronic device according to claim 78, wherein the connection comprises Sn, Ag, Bi and Cu.
- 82. An electronic device according to claim 78, wherein the lead is made of an Fe-Ni alloy, and a Cu layer is provided between the lead and the Sn-Bi alloy layer.

83. An electronic device comprising:

a semiconductor device having an electrode structure which comprises a lead and a Sn-Bi alloy layer containing 1-5 wt% Bi which is formed directly on the lead; and

a circuit board which is connected to the semiconductor device with a solder which is made of a Pb-free alloy,

wherein the connection is formed by soldering during which the solder is initially in contact with the Sn-Bi alloy and subsequently melted, whereby the Sn-Bi alloy is melted and mixed with the solder under heat from the solder.